

1 1. A method comprising:
2 exposing a semiconductor wafer to bidentate
3 chelating ligands; and
4 removing metal complexes formed by those
5 chelating ligands.

1 2. The method of claim 1 wherein removing metal
2 complexes includes volatilizing the metal complexes.

1 3. The method of claim 1 wherein removing the metal
2 complexes includes using supercritical carbon dioxide to
3 remove said complexes.

1 4. The method of claim 1 including removing said
2 metal complexes as a vapor.

1 5. The method of claim 1 wherein removing said metal
2 complexes includes removing three bidentate chelating
3 ligands per metal center.

1 6. A method comprising:
2 exposing a semiconductor wafer to chelating
3 ligands; and
4 removing a vapor including the chelating ligands
5 and a metal center.

1 7. The method of claim 6 wherein removing metal
2 complexes includes volatilizing the metal complexes.

1 8. The method of claim 6 wherein removing the metal
2 complexes includes using supercritical carbon dioxide to
3 remove said complexes.

1 9. The method of claim 6 wherein removing said metal
2 complexes includes removing three bidentate chelating
3 ligands per metal center.

1 10. The method of claim 6 including exposing said
2 wafer to bidentate chelators.

1 11. The method of claim 10 including exposing the
2 wafer to bidentate O,O' chelators.

1 12. The method of claim 10 including exposing said
2 wafer to N,N' chelators.

1 13. The method of claim 10 including exposing said
2 wafer to P,P' chelators.

1 14. A cleaning composition comprising:
2 supercritical carbon dioxide; and
3 bidentate chelating ligands.

1 15. The composition of claim 14 wherein said ligands
2 are N,N' chelators.

1 16. The composition of claim 14 wherein said ligands
2 include O,O' chelators.

1 17. The composition of claim 14 wherein said ligands
2 include P,P' chelators.

1 18. A method comprising:
2 volatilizing chelators; and
3 exposing a semiconductor wafer to said
4 volatilized chelators.

1 19. The method of claim 18 including volatilizing
2 bidentate chelators.

1 20. The method of claim 18 including removing metal
2 complexes formed by the chelators.